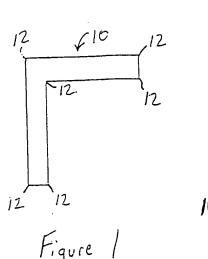
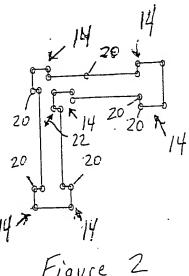
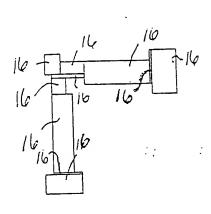
## REPLACEMENT SHEET









## Post-OPC layout

Modifying a polygon shape based on reticle CD specifications to provide a statistical virtual mask, such as statistically varying layouts which have passed through an OPC procedure, by moving fragments of a polygon, such as in fig.2, or by re-sizing primitives of a polygon, such in fig.3.

Constructing response functions based on the virtual mask imaging, such as simulating an aerial or latent image of a virtual mask, collecting simulated image critical dimensions (CDs), calculating statistical parameters of simulated CDs (image response to the reticle CD errors), and comparing the statistical response with process tolerance requirements

Figure 4.



## REPLACEMENT SHEET

Means (software) for modifying a polygon shape based on reticle CD specifications to provide a statistically modified virtual mask, such as statistically varying layouts which have passed through an OPC procedure, by moving fragments of a polygon, such as in fig.2, or by resizing primitives of a polygon, such in fig.3.

Means for constructing response functions based on the virtual mask imaging, such as simulating an aerial or latent image of a virtual mask, collecting simulated image critical dimensions (CDs), calculating statistical parameters of simulated CDs (image response to the reticle CD errors), and comparing the statistical response with process tolerance requirements

Figure 5.